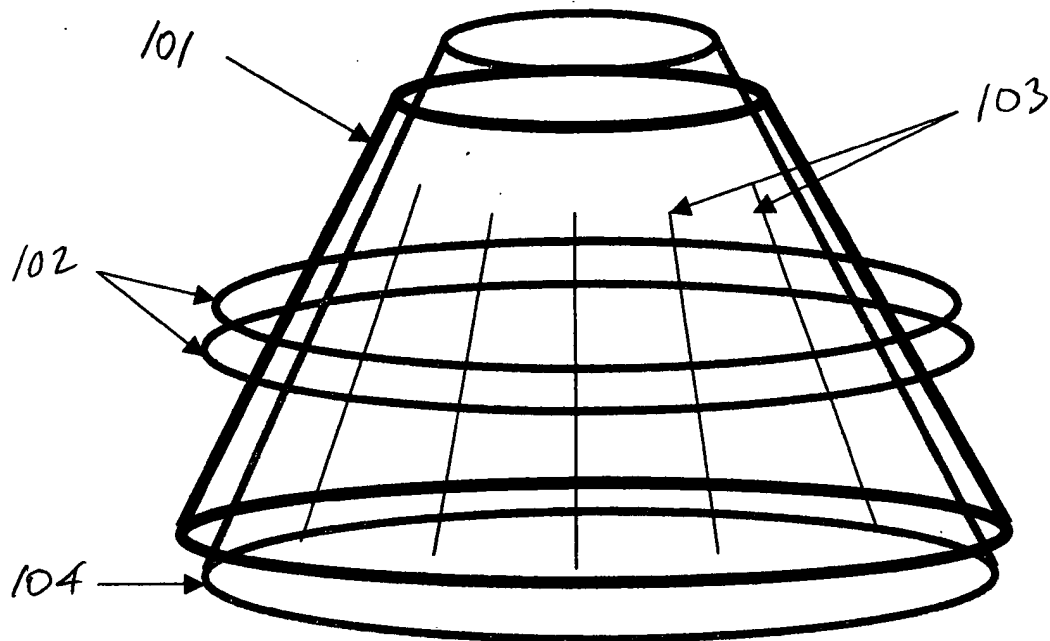


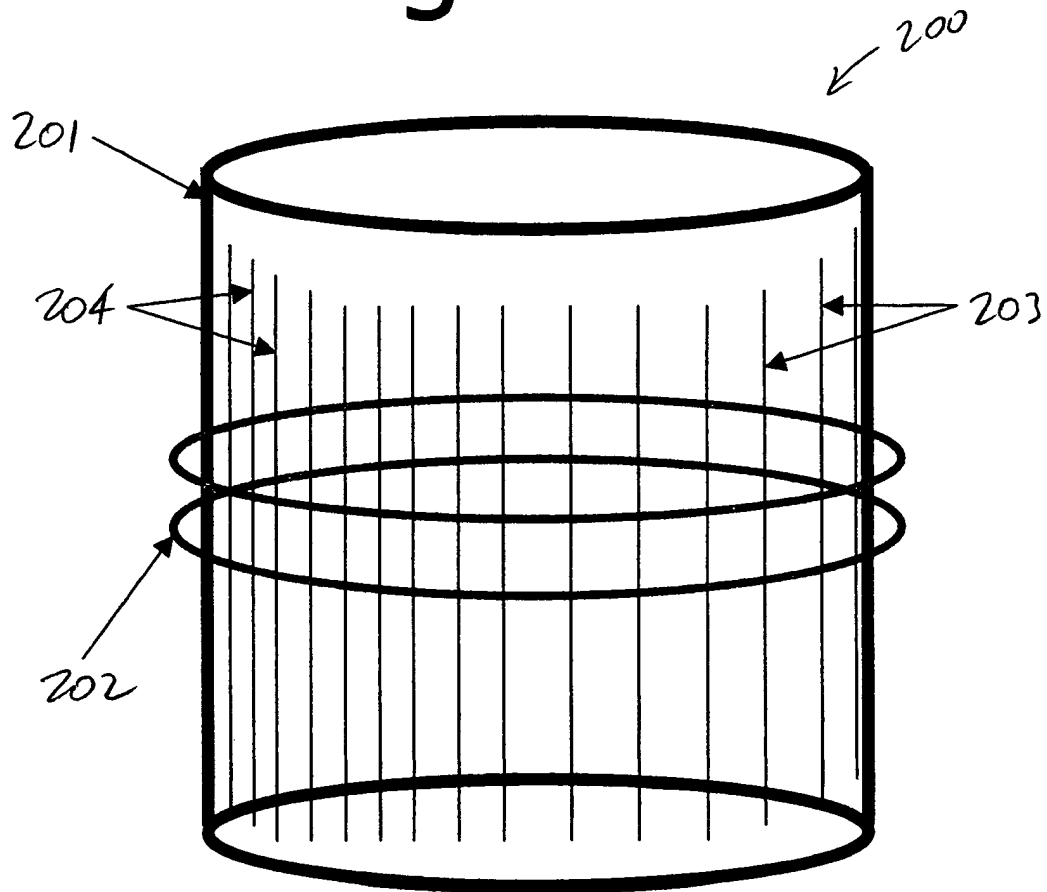
Figure 1



(Prior Art)

The Slotted Electrostatic Shield is seen here with a truncated cone Shape. The Shield fits closely over the plasma vessel shown as the taller and narrower cone.

Figure 2



The shield shown in Figure 2 has a higher density of slots on the left side than on the right in order to permit RF power penetration on the left to be greater than on the right which will improve process uniformity if the RF current in the coil is less on this side than on the right.

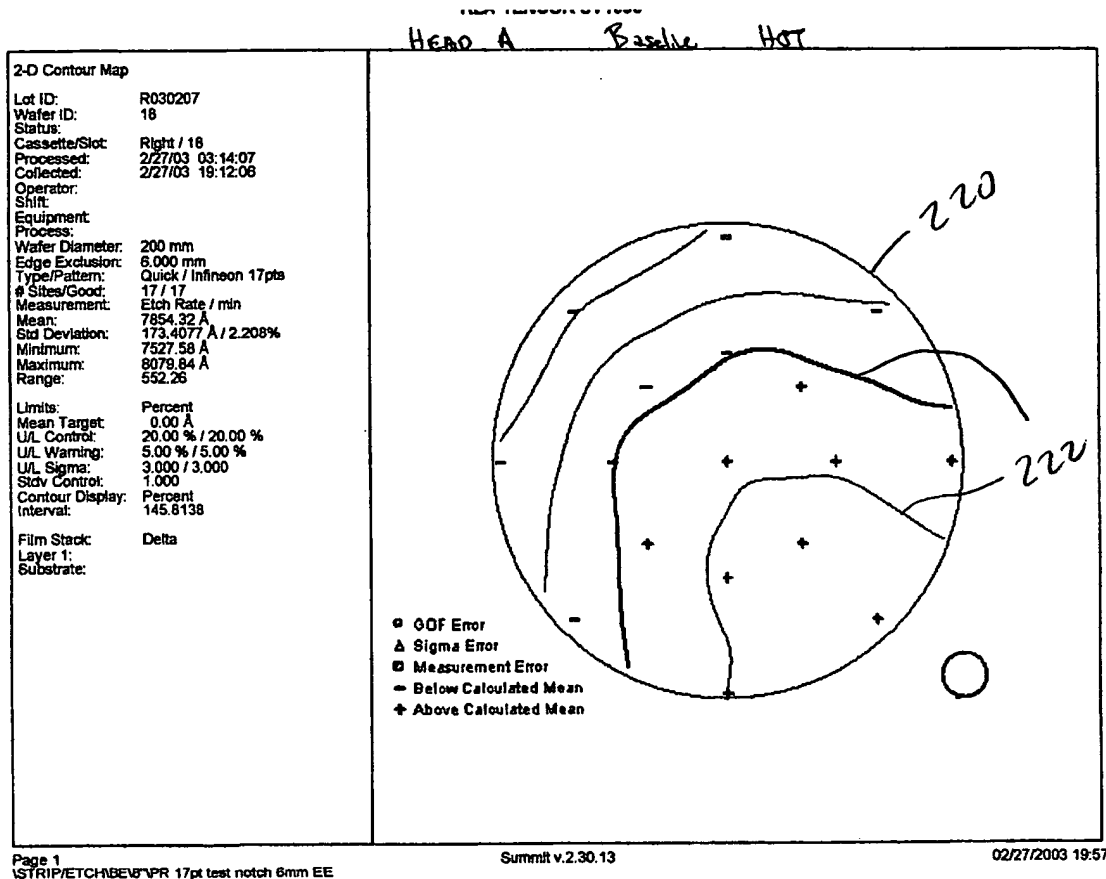


Figure 3a

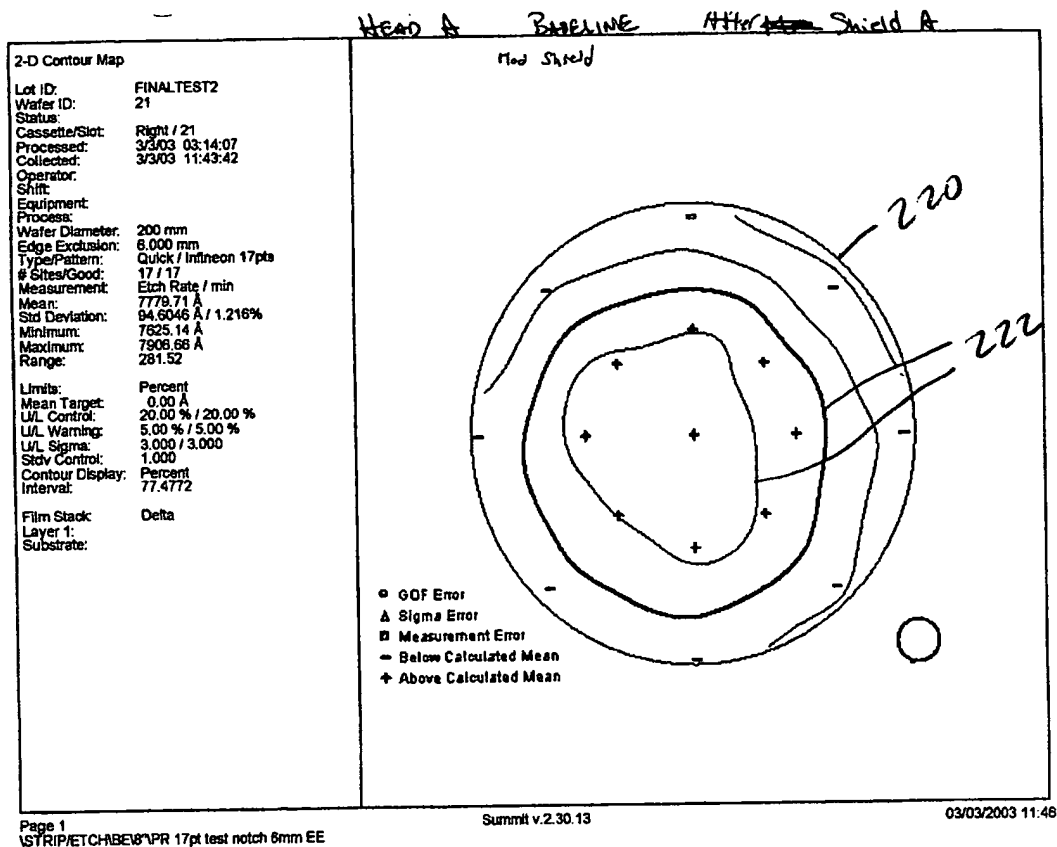
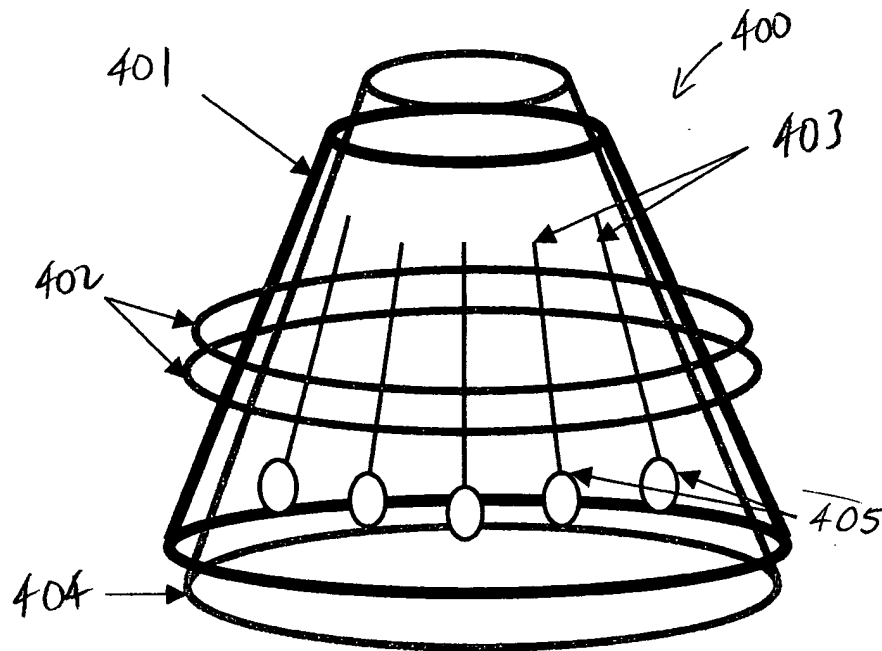


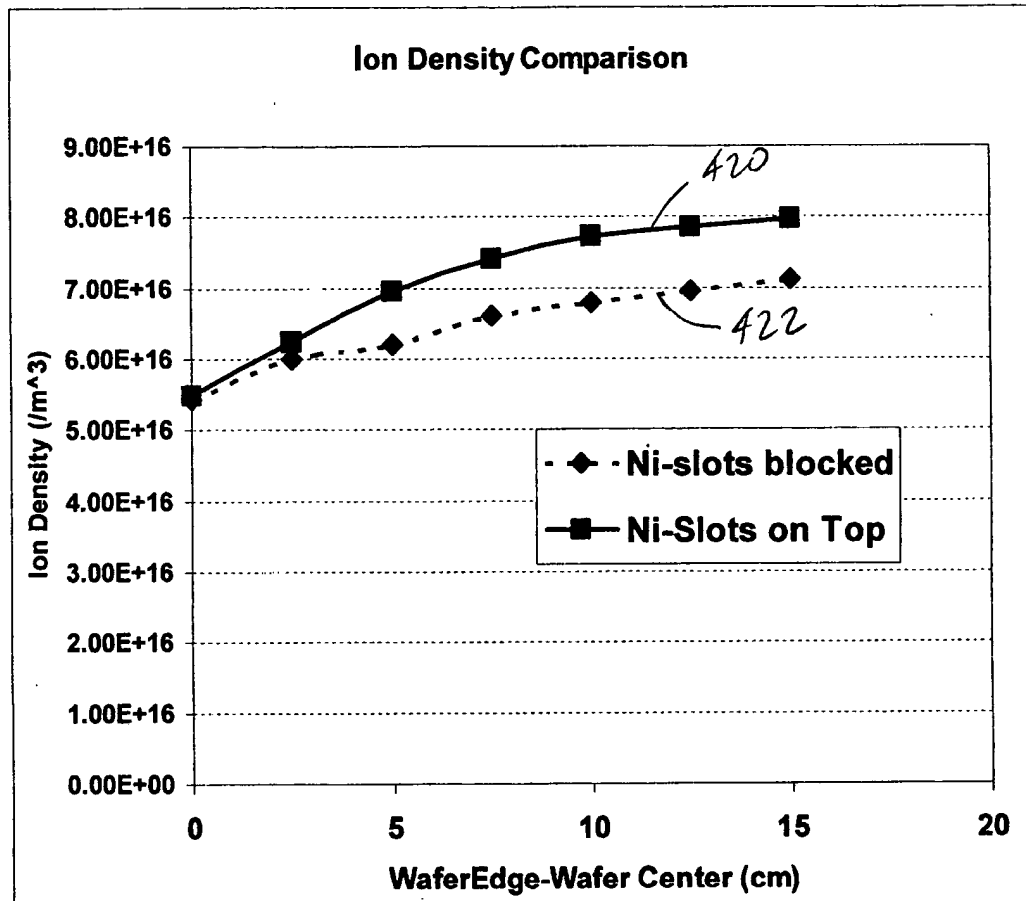
Figure 3b

Figure 4



The Slotted Electrostatic Shield is seen here with a truncated cone Shape. The Shield fits closely over the plasma vessel shown as the taller and narrower cone.

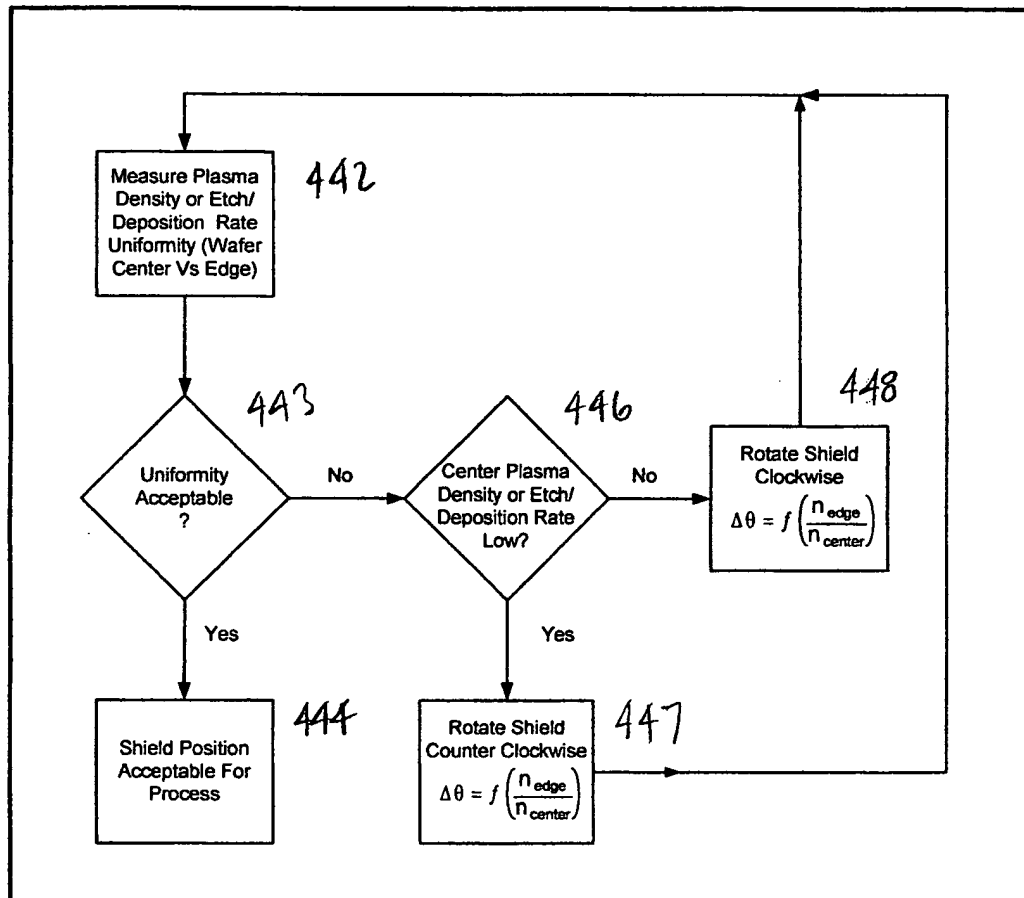
Figure 5



The ion density measured from the edge of the wafer to the center shows a reduction in the center density when the end of the slots closer to the center of the source are blocked.

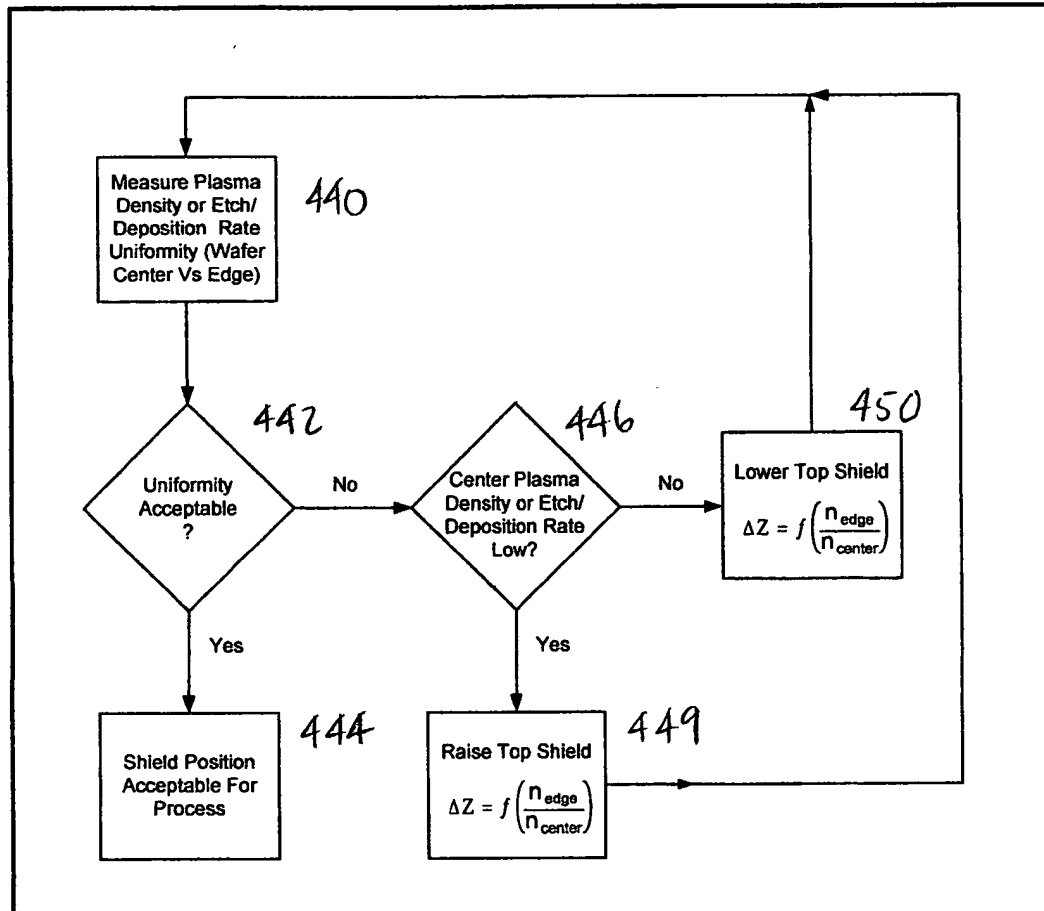
Figure 6a

440



Control Scheme for Rotatable Outer Shield

Figure 6b



Control Scheme for Variable Gap Shield

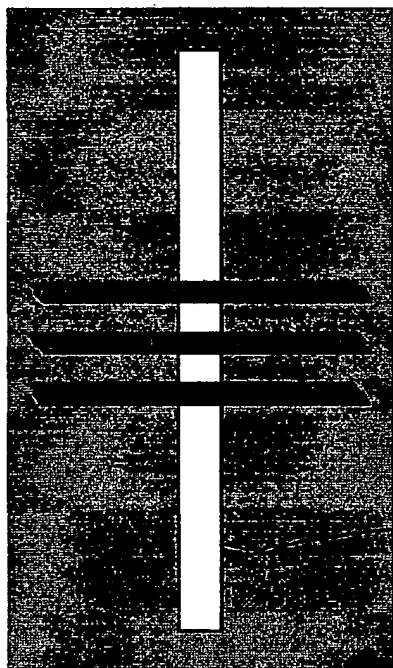


Figure 7a

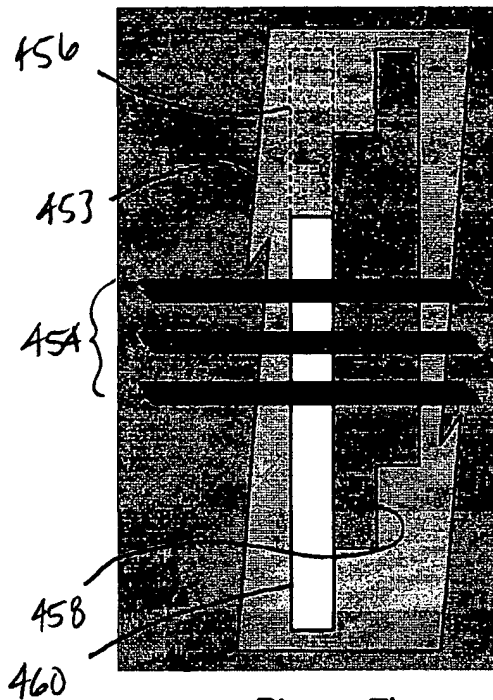


Figure 7b

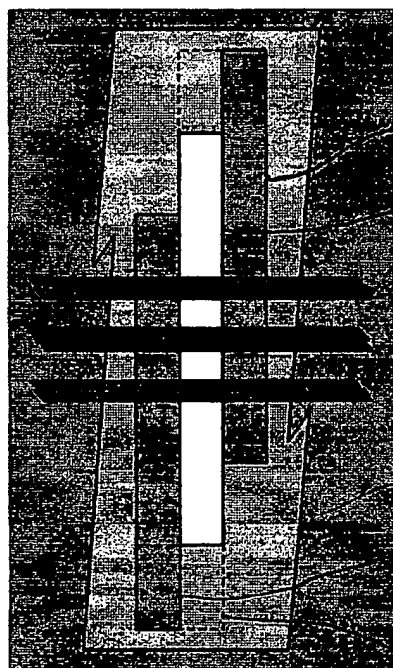


Figure 7c

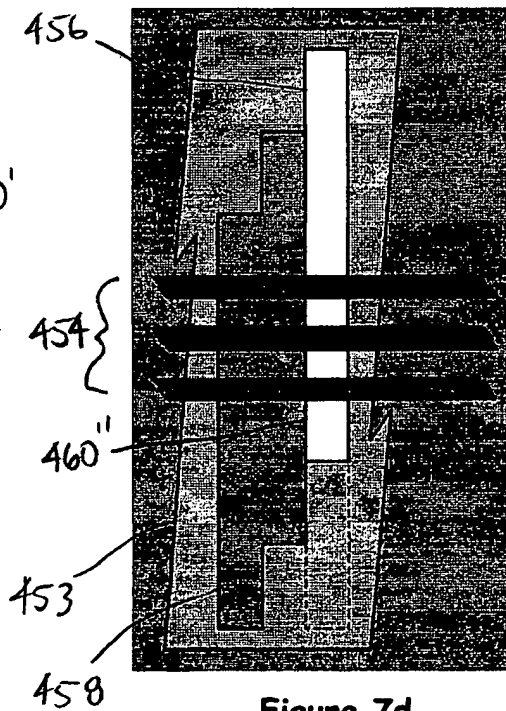


Figure 7d

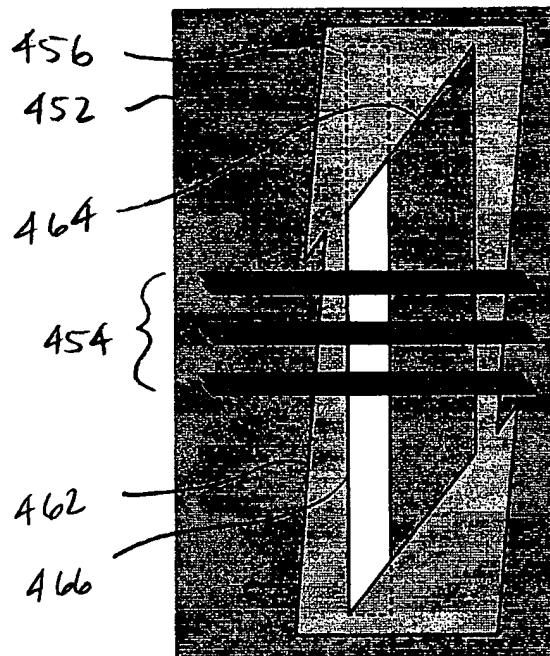


Figure 7e

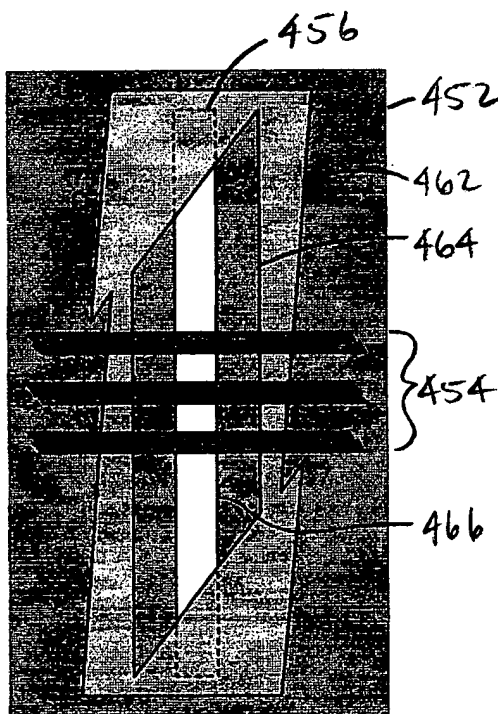


Figure 7f

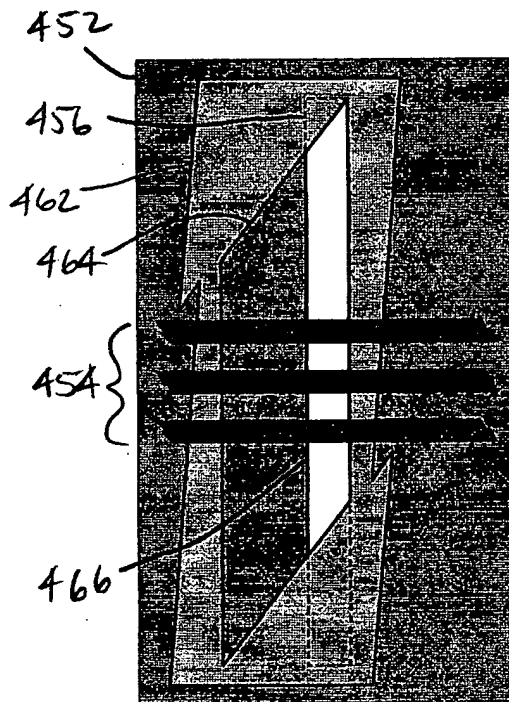


Figure 7g

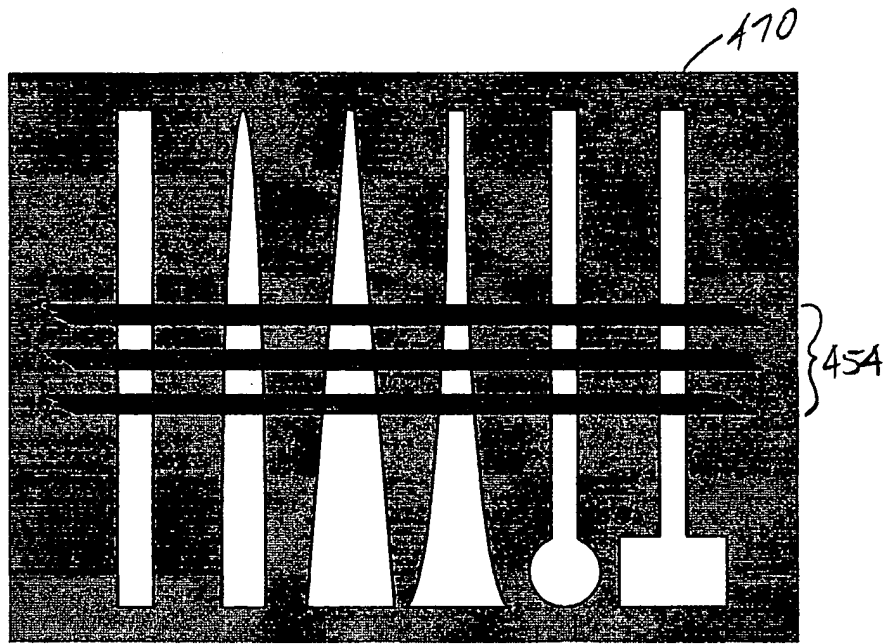


Figure 8a

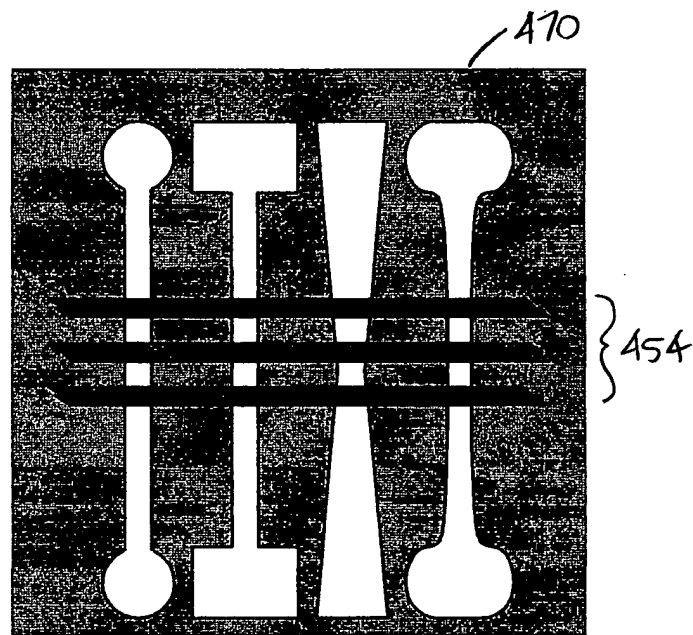
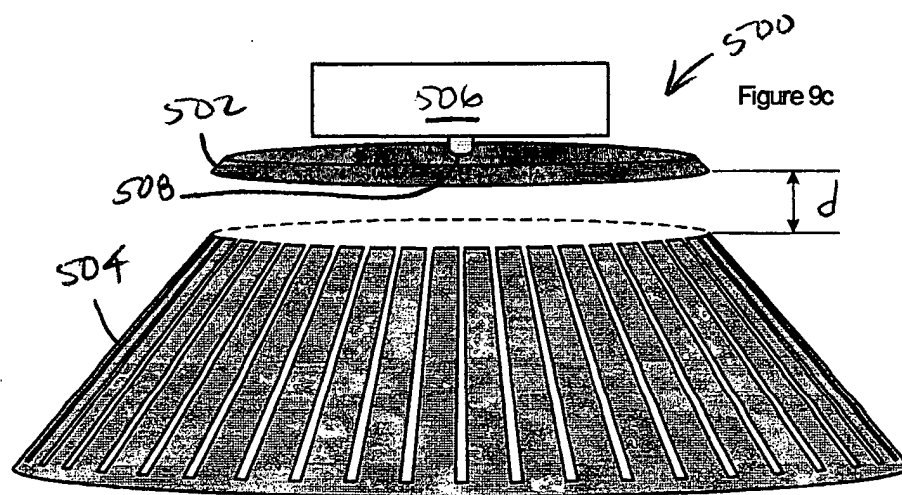
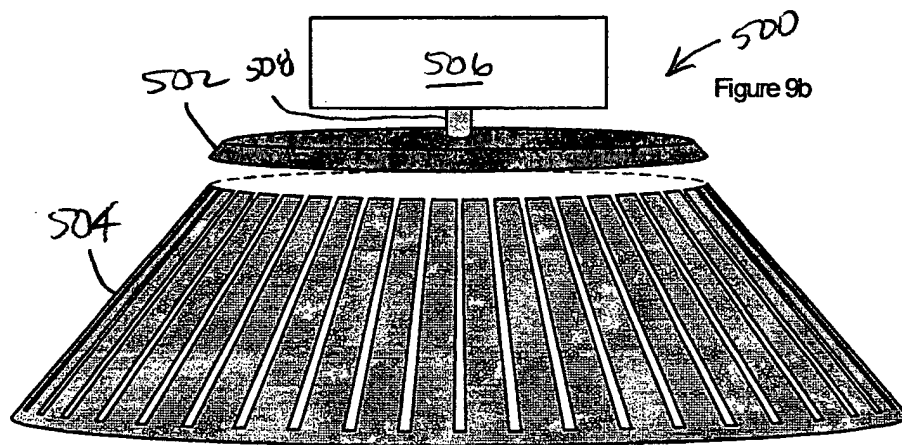
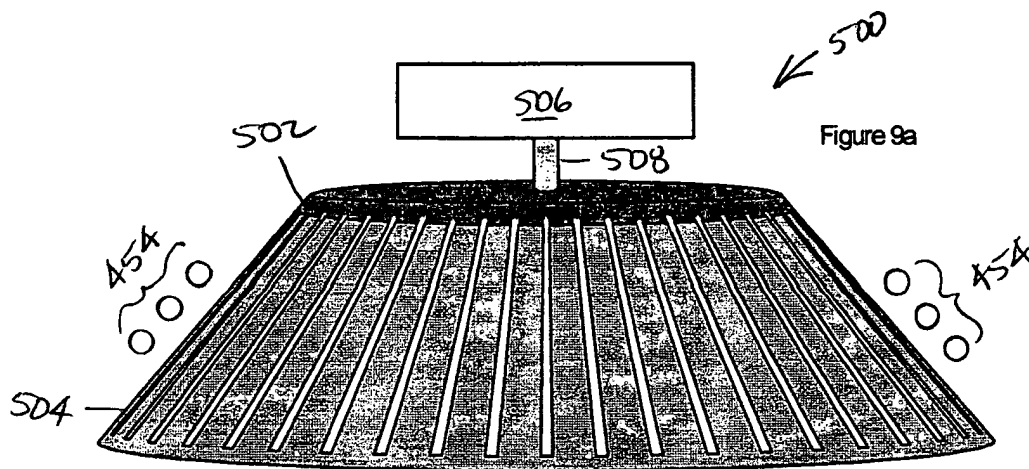


Figure 8b



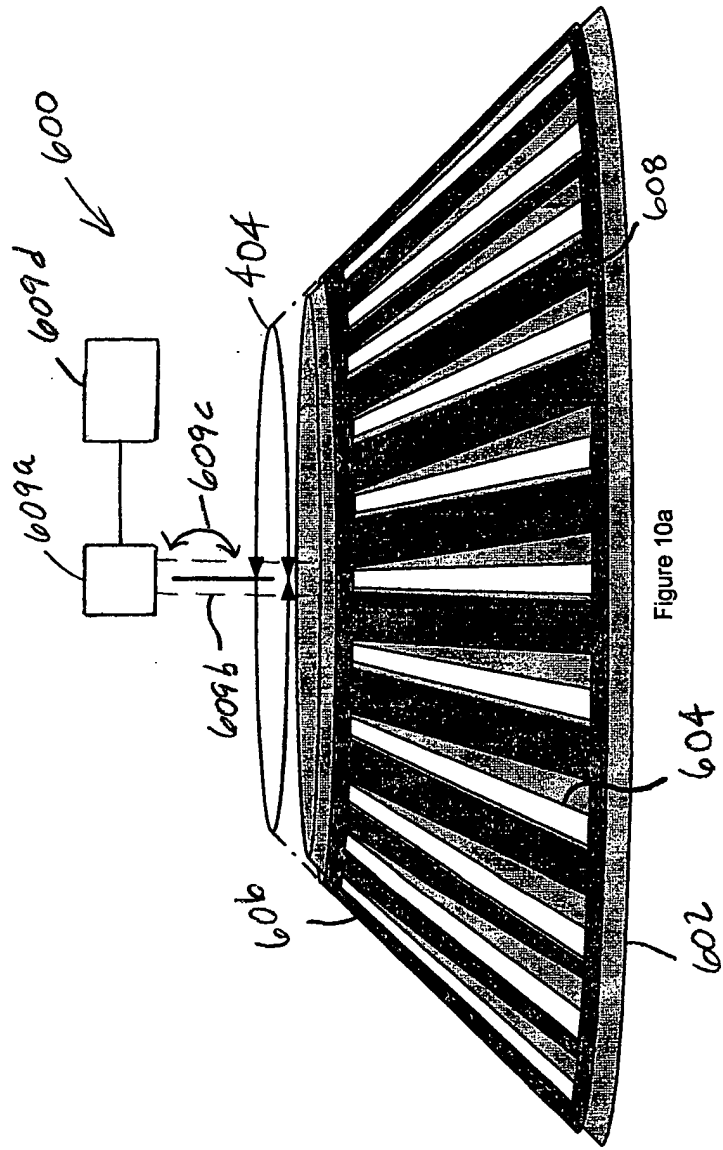
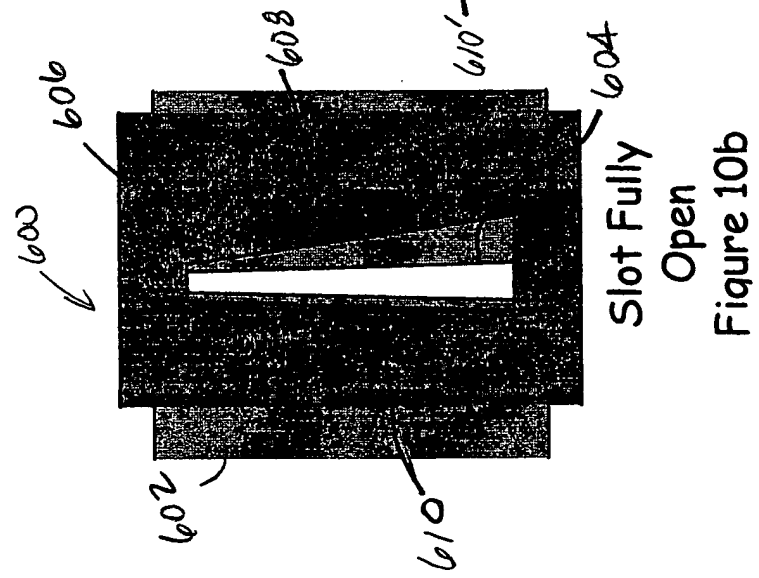
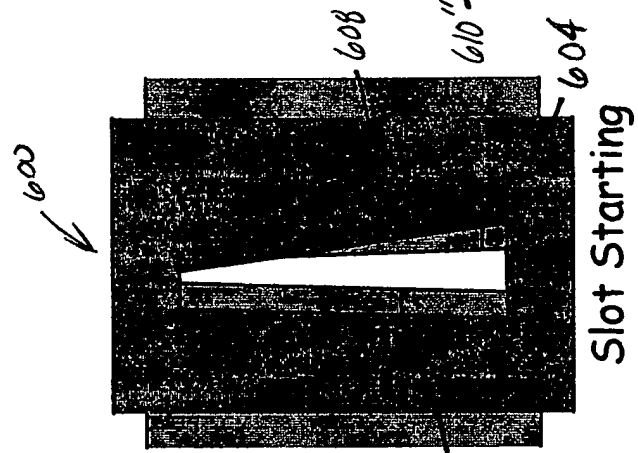


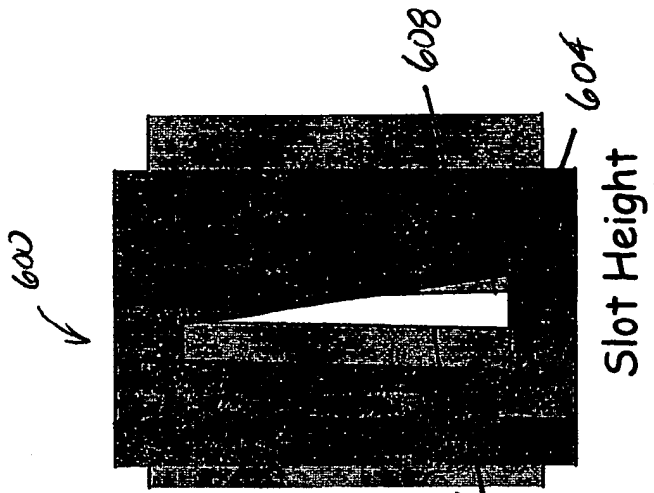
Figure 10a



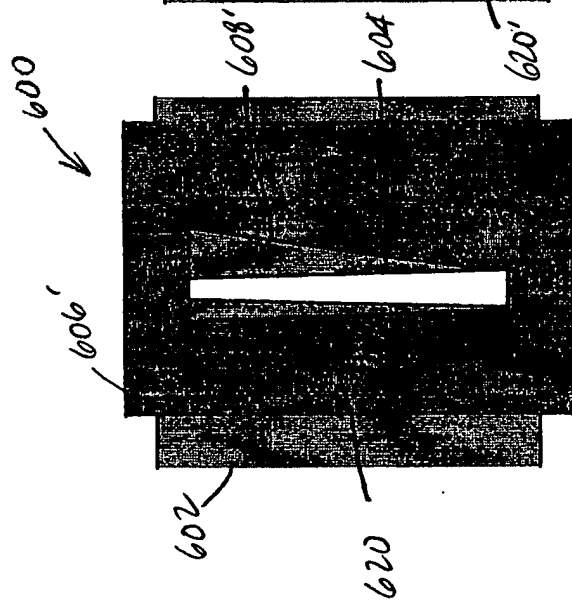
Slot Fully
Open
Figure 10b



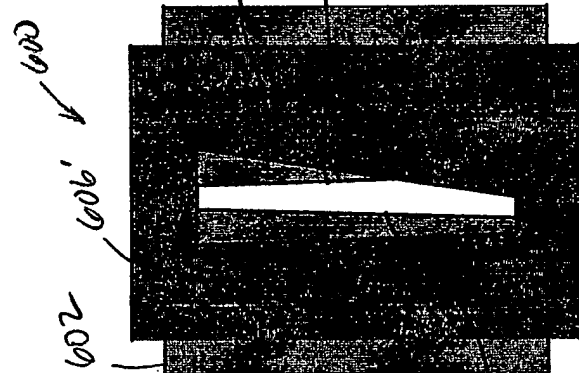
Slot Starting
to Close
Figure 10c



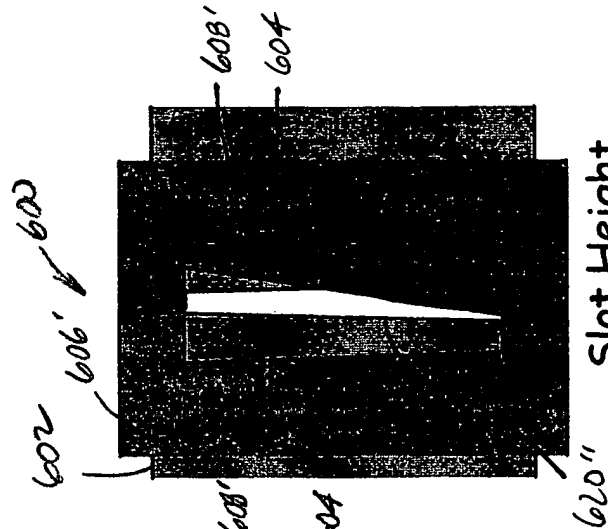
Slot Height
Reduced
Figure 10d



Slot Fully
Open
Figure 10e



Slot Starting
to Close
Figure 10f



Slot Height
Reduced
Figure 10g

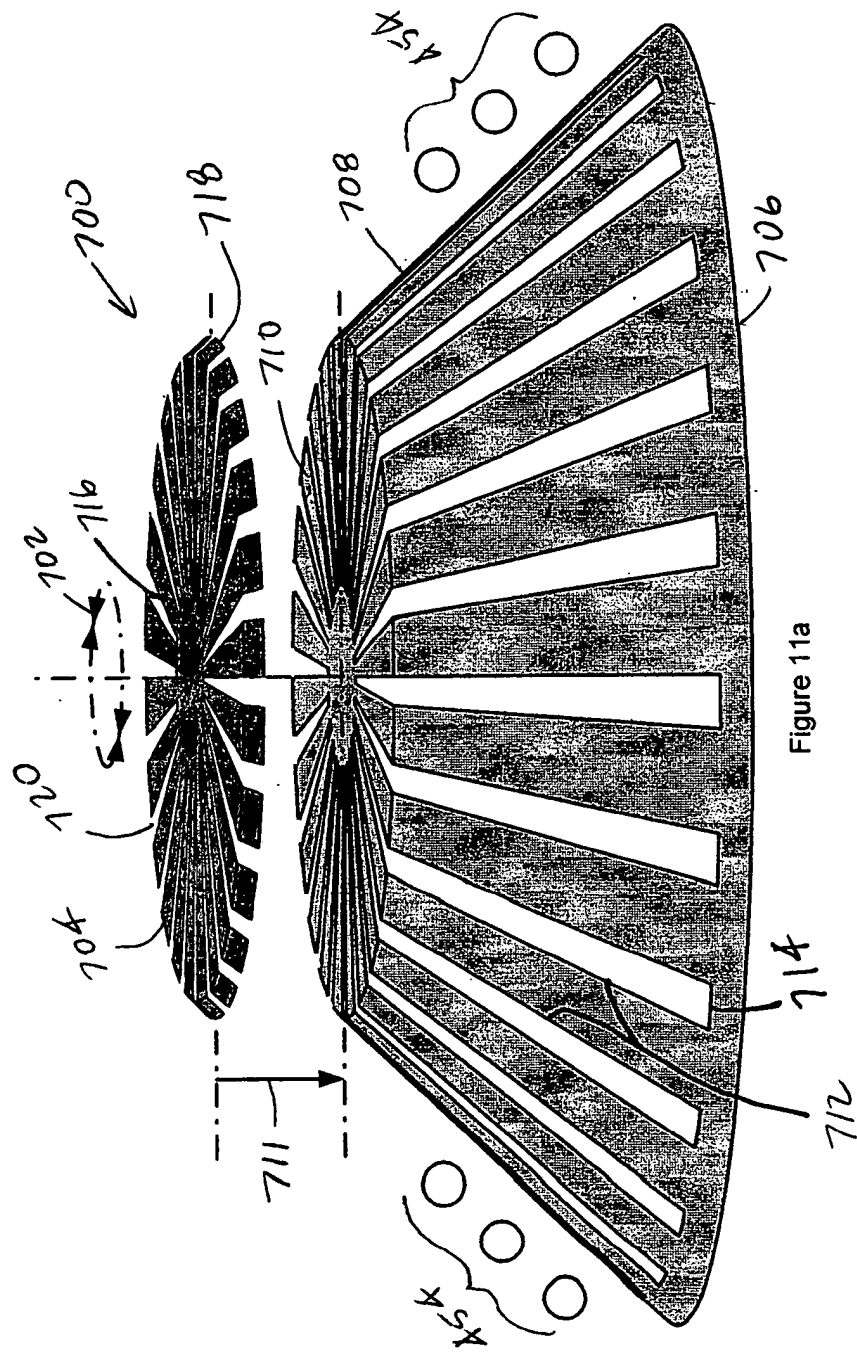


Figure 11a

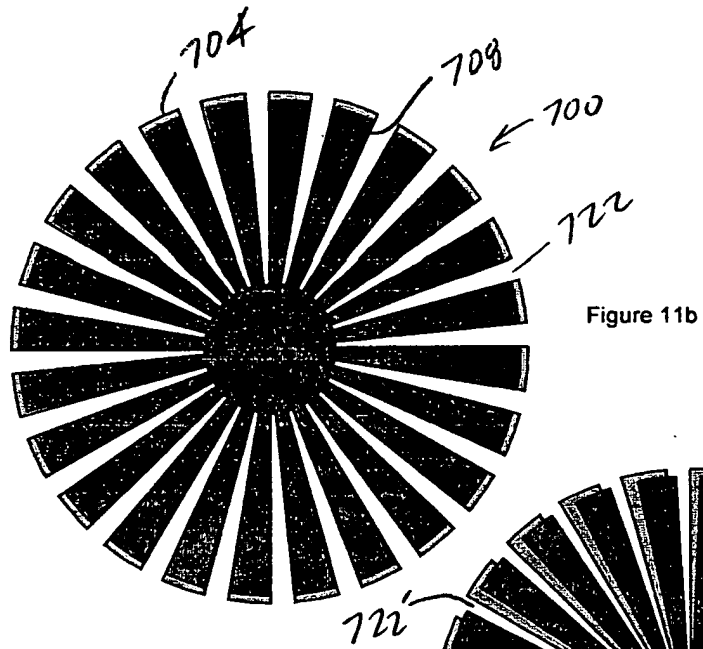
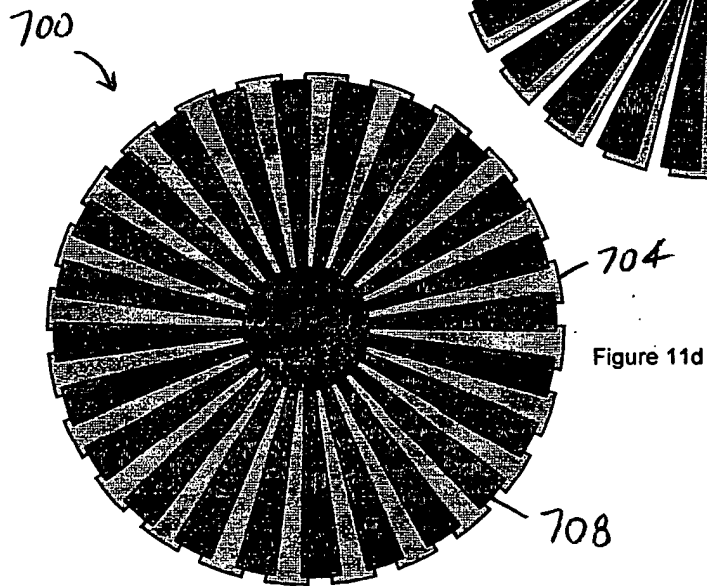
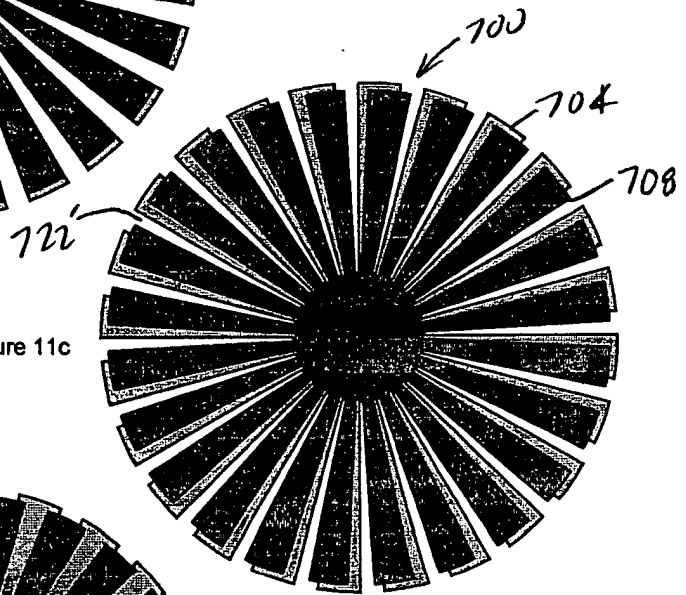
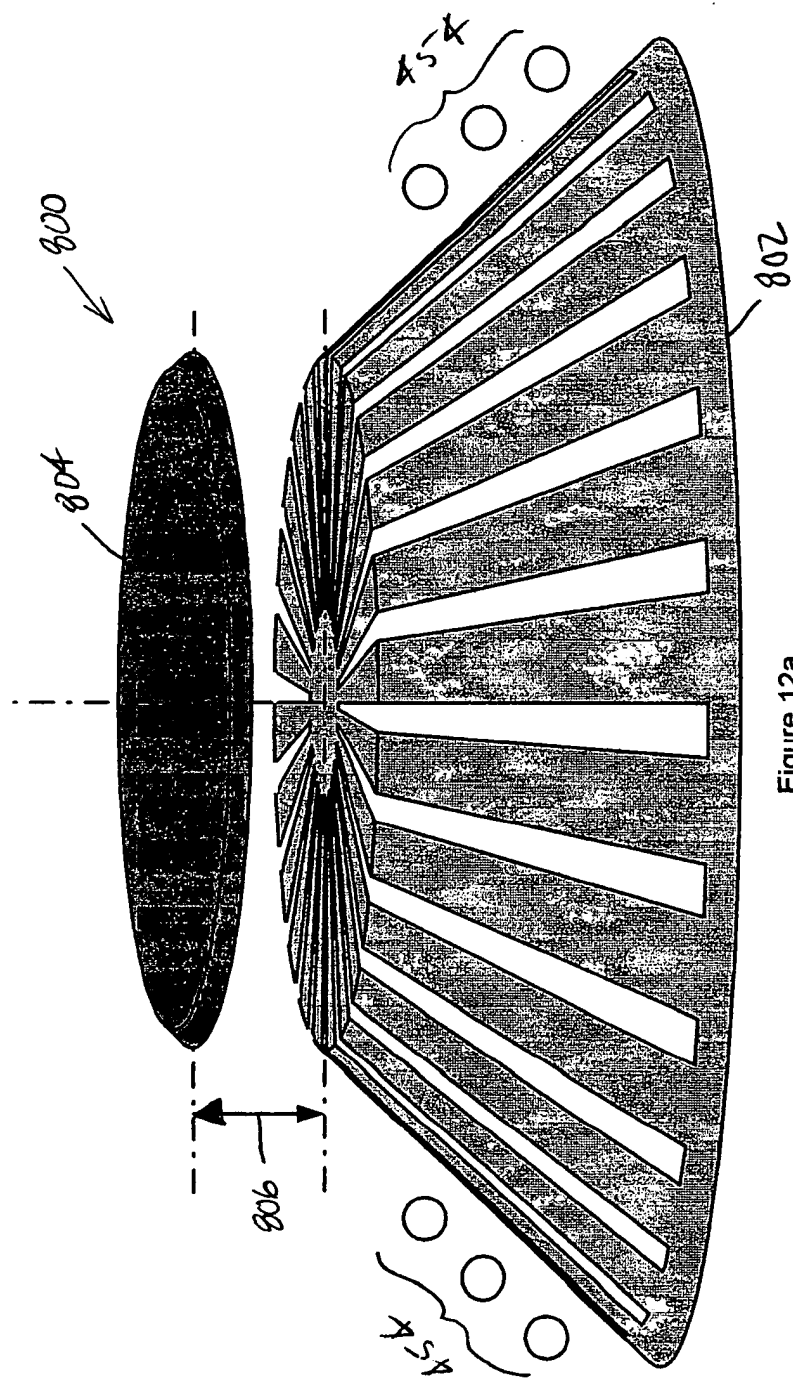


Figure 11c





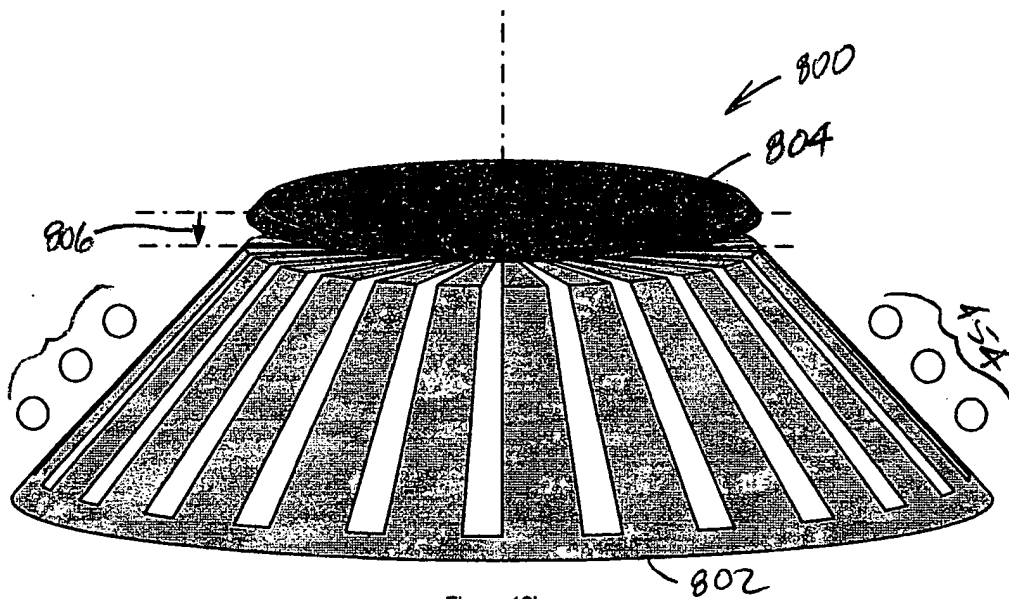


Figure 12b

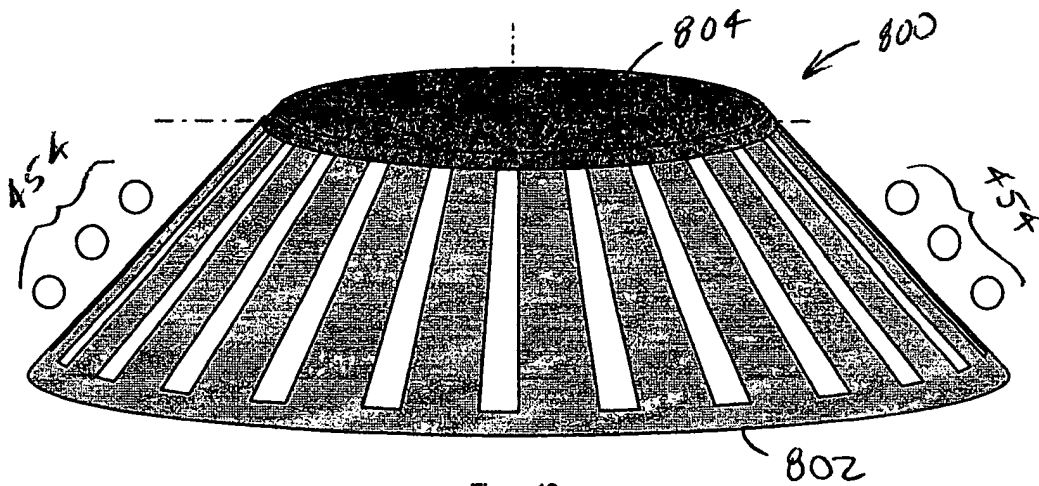


Figure 12c